Hall Pyke

No Image in Brochure

Surface Pre Filtration

FluoroPFA® Filter Cartridges

The SMART choice for filtration



FluoroPFA® Filter Cartridges

All-Polyfluorene Filter

Hall Pyke FluoroPFA® Filter Cartridges utilize expanded PTFE membranes and PFA core & cage to meet critical filtration requirements in extremely aggressive environments. PFA Filters remain strong and durable in aggressive acids, bases, and organic compounds. In addition, hydrophilic PTFE membranes require no pre-wetting.

Features and Benefits

- All-fluoropolymer material of construction provides superior resistance during chemical processing and pulsing.
- · Excellent chemical compatibility.
- · High temperature and pressure capabilities.
- Very high flow rates with low differential pressure.
- · Low extractable.
- · High particle removal efficiency.
- · Manufactured in a clean room environment.

Typical Applications

- Highly corrosive Acids, such as Hydrofluoic Acid, Nitric Acid and Sulfric Acid.
- High Temperatures Chemical Liquid (>100°C).
- · Aggressive Solvents, such as Chloroform, Two methyl, Isopropyl Alcohol.
- · Aggressive Bases.
- · Oxidizing Air/Gas.

All-Polyfluorene Filter

Materials of Construction

Filter Media PTFE Membrane Support Laver PFA

Support Layer PFA Core/Cage/End Caps PFA

O-rings Teflon® Encapsulated Viton® Effective Filtration Area 0.7m²/Ф68mm 10 inch

0.7m²/Φ68mm 10 inch 1.5m²/ Φ83mm 10 inch

Max. Operating Temperature 170°C

Max.Differential Pressure 4bar/50°C

3bar/110°C 1.5bar/170°C

Removal Ratings

1.0µm, 3.0µm, 5.0µm, 10µm

Chemical Compatibility

Chemical	EPP Series	PFA Series	APTF Series	AET Series	LPF Series
Acetic Acid (10%)	G	E	E	E	E
Hydrofluoric Acid (50%)	G	E	E	E	E
Hydrogen Peroxide (30%)	LR	E	G	LR	G
Nitric Acid (conc.)	NR	E	NR	NR	NR
Phosphoric Acid (conc.)	LR	E	G	E	G
Sulfuric Acid (conc.)	NR	E	NR	LR	LR
Ammonium Hydroxide (conc.)	G	E	NR	NR	E
Potassium Hydroxide (conc.)	G	E	NR	LR	E
Sodium Hydroxide (conc.)	G	E	NR	LR	E
TMAH (5%)	G	E	NR	G	E
Aqua Ragia HNO₃:HCL	NR	E	NR	LR	NR
BEO; NH ₄ F:HF	G	E	E	G	G
Mixed Acid Etch HNO ₃ <20% (HNO ₃ : HF:CH ₃ CO ₂ H)	LR	E	LR	LR	LR
Chrom Phos (H ₂ O:H ₃ PO ₄ :CRO ₃)	LR	E	G	G	G
N-Methyl Pyrrolidone	LR	E	NR	G	G
Piranha (H ₂ SO ₄ O ₂)	NR	E	NR	LR	NR
RCA Etch	NR	E	G	G	G
SC1 (RCA Clean)	NR	E	NR	LR	LR
SC2	NR	E	NR	LR	LR

E = Excellent G = Good at Ambient Temperatures LR = Lim The above data is to be used as a guide only. Testing prior to application is recommended.

LR = Limited Resittance

NR = Not Recommended

Hall Pyke



www.hallpyke.ie